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#### CHEMICAL REDUCTION OF REFRACTORY OXIDES BY ATOMIC HYDROGEN

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Refractory oxides are utilized for a number of electrically insulating components in controlled thermonuclear reactors (1). These components are subjected to bulk radiation damage by high energy particles and, like graphite (2), may be susceptible to surface chemical attack by deuterium and tritium. The nature of the chemical attack of 110, and Al<sub>2</sub>O<sub>3</sub> by thermal energy atomic hydrogen has been investigated by the modulated molecular beam-mass spectrometer technique (3,4). The experiment is conducted in the high vacuum system shown in Fig. 1. The reactant atomic hydrogen beam is produced by effusion from a hot (2500°K) dissociation oven. This beam is modulated by a mechanical chopper prior to striking the solid surface. Desorbed reaction products (water vapor and perhaps lower oxides or the metallic component of the target) and scattered atomic hydrogen are detected in flight by a quadrupole mass spectrometer. The main quantity which is measured is the reaction probability, which is defined as the rate of desorption of a reaction product divided by the rate of impingement of the reactant. The reaction probabilities reported here refer to the signal ratio of water to atomic hydrogen detected by the mass spectrometer. The modulated aspect of the experimental technique serves to enhance the signal-to-noise ratio of the method and also provides information on surface residence times which is very valuable in deducing a detailed mechanism of the surface reaction. The two model oxides selected for this investigation, UO2 and Al2O3, are the best characterized of any oxides; their physical and thermochemical properties are reasonably well known and there have been many investigations of their vacuum vaporization behavior and their reactivity with other gases. The basic difference between

the two oxides is the possibility of formation of nonstoichiometric compounds. Urania contains a cation which exhibits multiple valence states and thus can form a wide range of solid solutions of the  $\mathrm{UO}_{2\pm x}$  type which retain the basic fluorite structure of  $\mathrm{UO}_2$ . The aluminum ions in alumina, however, possess only +3 valence, so aluminia is essentially a line compound with practically no deviation from the formula  $\mathrm{Al}_2\mathrm{O}_3$  whether the environment is oxidizing or reducing.

Results of the  $\mathrm{UO}_2/\mathrm{H}$  investigation indicates that reduction of  $\mathrm{UO}_2$  by atomic hydrogen-proceeds by the production of water vapor and hypostoichiometric urania:

$$\frac{1}{x}$$
 UO<sub>2</sub> + 2H +  $\frac{1}{x}$  UO<sub>2-x</sub> + H<sub>2</sub>O(g) (1)

The reaction probability for water production as a function of UO<sub>2</sub> temperature was measured at a fixed H atom beam intensity and modulation frequency. The reaction probability increased from the noise level at low temperatures to a high temperature plateau at about 1300°C. At the plateau, approximately one H atom out of seven striking the surface undergoes reaction and returns to the gas phase as water.

Contrary to  ${\rm UO}_2$ , the range of deviation from stoichiometry of  ${\rm Al}_2{\rm O}_{3-x}$  is probably so small that even slight reduction of  ${\rm Al}_2{\rm O}_3$  requires production of the metal. Because alumina cannot be rendered hypostoichiometric, its reduction by atomic hydrogen results in production of aluminum metal:

$$\frac{1}{3} \Lambda 1_2 O_3 + 2H + \frac{7}{3} \Lambda I + H_2 O(g)$$
 (2)

The results of our study of the  $Al_2O_3/H$  system indicate that the reaction does indeed proceed according to Eq(2). However, the observed reaction probability for water production remains too low to be detected (i.e., <  $10^{-3}$ ) until the temperature is greater than  $1300^{\circ}$ C. At higher temperatures, both  $H_2O$  and aluminum are detected by the mass spectrometer as gaseous reaction products. Other products, such as AlO, AlH, AlOH, Al $_2O$  and  $Al_2OH$  were sought but not found. The reaction probability increases with temperature, but remains two orders of magnitude below the maximum value for the  $UO_2/H$  reaction.

The relative ease which  $\mathrm{UO}_2$  is reduced by atomic hydrogen compared with  $\mathrm{Al}_2\mathrm{O}_3$  is due to two factors. The first is related to the thermochemistry of reactions (1) and (2). Although thermodynamics cannot be invoked to predict chemical kinetics, one can at least expect that thermochemically favored reactions should be the most readily observed.

A rough estimate of the ease of reducing Al<sub>2</sub>O<sub>3</sub> by atomic hydrogen can be obtained from the standard free energy change of reaction (2), which is:

$$^{\Lambda G^{\circ}}_{(2)} \ = \ - \ \frac{1}{2} \Delta G^{\circ}_{A1}{}_{2}O_{3} \ - \ 2\Delta G^{\circ}_{H} \ + \ \Delta G^{\circ}_{H_{2}O}$$

where  $\Lambda C_{11}^{\circ}$  and  $\Lambda C_{12_0}^{\circ}$  are the standard free energies of formation of atomic hydrogen and water, respectively, and  $\Lambda G_{\Lambda 1_{2}O_{3}}^{\circ}$  is the free energy of formation of alumina (per mole of  $O_{2}$ ). The equilibrium oxygen pressure over the  $\Lambda I/\Lambda I_{2}O_{3}$  couple is given by:  $\Lambda G_{\Lambda 1_{2}O_{3}}^{\circ} = RTInp_{O_{2}}$  where R is the gas constant. The comparable quantity of  $UC_{2}$  is the oxygen potential  $\overline{\Lambda G_{O_{2}}}$ . Hence, the standard free energy change for reaction (1) for small x is:

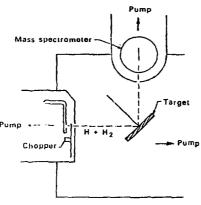
$$\Delta G_{(1)}^{\circ} = -\frac{1}{2} \overline{\Delta G_{0_2}} - 2\Delta G_H^{\circ} + \Delta G_{H_2O}^{\circ}$$

The free energy change of reaction (1) at 1000 K is -310 kJ/mole, whereas that of reaction (2) is -71 kJ/mole. The fact that both of these free energy changes are substantially negative suggest that, barring kinetic restrictions, reduction of the oxides should proceed in atomic hydrogen. However, urania should be easier to reduce than alumina because removal of oxygen from NO<sub>2</sub> coes not require production of the metal.

The second reature which favors efficient reduction of  $\mathrm{UO}_2$  but not of  $\mathrm{Al}_2\mathrm{O}_3$  is the oxygen diffusivity. As the reduction reaction proceeds at the surface, oxygen depletion of the surface layers will quickly stop the reaction unless oxygen can be transported to the surface from the bulk solid. The self-diffusion coefficient of oxygen in hypostoichiometric urania has not been measured, but is probably very large (5), whereas oxygen migration in alumina is smaller, probably by many orders of magnitude (6). Consequently, oxygen transport from the interior of the solid to the reacting surface takes place easily in  $\mathrm{UO}_2$  but in alumina, evaporation of the aluminum metal reaction product appears to be necessary to prevent a protective scale of Al from halting the surface reduction process.

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